

| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|-------|--------|---|--|------------------|---------|------------------|
| L1 | 242611 | phenol\$2 or polyvinylphenol\$2 or hydroxystyrene or polyhydroxystyrene | US-PGPUB; USPAT | OR | ON | 2005/02/20 17:39 |
| L2 | 2921 | (phenol\$2 or polyvinylphenol\$2 or hydroxystyrene or polyhydroxystyrene) same anthracene | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/02/20 17:39 |
| L3 | 8416 | barc or antireflective | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/02/20 17:40 |
| L4 | 48 | 2 and 3 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/02/20 18:02 |
| L5 | 46186 | photoresist same (si or silicon) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/02/20 18:04 |
| L6 | 1246 | photoresist same photoacid | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/02/20 18:03 |
| L7 | 664 | 5 and 6 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/02/20 18:03 |
| L8 | 11 | 4 and 7 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/02/20 18:24 |
| L9 | 35070 | (polymer or resin) near3 (silicon or trimethylsilicon or trimethylsilyl) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/02/20 18:35 |

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| L10 | 50 | 3 and 9 and 7 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/02/20 18:26 |
| L11 | 4 | 4 and 7 and 9 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/02/20 18:27 |
| L12 | 3 | (polymer or resin) near 3 (trimethylsilylmethacrylate or trimethylsilylacrylate) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/02/20 18:38 |
| L13 | 0 | (photoresist) near 3 (trimethylsilylmethacrylate or trimethylsilylacrylate) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/02/20 18:38 |
| L14 | 0 | (photoresist) same (trimethylsilylmethacrylate or trimethylsilylacrylate) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/02/20 18:39 |
| L15 | 17 | (polymer or resin) same (trimethylsilylmethacrylate or trimethylsilylacrylate) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/02/20 18:57 |
| L16 | 3073 | (photoresist or resist adj composition) and (barc or antireflective) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/02/20 18:40 |
| L17 | 0 | 15 and 16 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/02/20 18:40 |

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| L18 | 0 | 3 and 17 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/02/20 18:58 |
| L19 | 526 | two adj layer adj resist | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/02/20 18:58 |
| L20 | 4 | 19 and 3 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/02/20 18:58 |